

Benchtop Plasma System

The PE-200 is a complete industrial grade plasma treatment solution – capable of plasma cleaning, plasma etching, reactive ion etching, and more.

This model is available in one of three possible configurations:

- 1) Plasma Cleaning/Plasma Etching
- 2) Reactive Ion Etching (RIE)
- 3) Convertible Configuration – Includes both isotropic and anisotropic plasma processing in a single system. Removable tray configuration.



STANDARD FEATURES

Electrode Configuration	Three Stacked Horizontal (13"Wx16"D + 3" Clearance)
Generator	300W 13.56MHz Continuously Variable Power Supply with Automatic Matching Network
Gas Control	One 0-200cc Mass Flow Controller
Control System	Laptop Equipped with Plasma Etch Inc.'s Control Software for Fully Automatic System Operation
Vacuum Gauge	1-2000 mT
Vacuum Pump	29CFM 2-Stage Direct Drive Oil Pump (Oxygen Service – Krytox Charged)
Chamber	17" x 17" x 14"; 6061-T6 Aluminum
Unit Dimensions	18" x 19" x 24"
Unit Weight	350lbs; 500lbs with Vacuum Pump

FACILITY REQUIREMENTS

Electrical	120V/208VAC (Five Wire, Three Phase) or 208VAC (Four Wire, Three Phase)
Compressed Air Service	80-100PSI, 0.5CFM
Regulated Process Gases	15PSI, 2-Stage Regulator

OPTIONAL FEATURES

- Custom Vacuum Chamber or Electrode Size
- Reactive Ion Electrodes
- MHz Power Supplies with Automatic Matching Network
- PC-Based Control System
- Electrostatic Shielding
- Temperature Control System
- Dry Vacuum Pump
- Chiller System for Dry Vacuum Pump
- Chamber and Vacuum Pump Purge Systems
- Vacuum Pump Oil Mist Eliminator
- Vacuum Pump Oil Filtration
- Automatic Vacuum Control
- Additional Digital Mass Flow Controllers
- Software Configurable Gas Steering Matrix 2x5
- Low Gas-Source Alarm
- Light Tower
- Fume Scrubber